

WHAT IS CLAIMED IS

1. An electrodeposited copper foil wherein part of its surface comprises a rough surface having knob-like projections and a surface roughness of 2 to 4 μm .

5 2. An electrodeposited copper foil as set forth in claim 1, wherein said rough surface having said knob-like projections and said surface roughness of 2 to 4 μm is a surface of an untreated copper foil for bonding with a resin substrate and is further roughening treated by
10 running a predetermined current through the foil for a predetermined time in an electroforming bath.

3. An electrodeposited copper foil as set forth in claim 2, wherein said electroforming bath is an acidic electroforming bath containing at least one of molybdenum,
15 cobalt, nickel, iron, tungsten and arsenic.

4. An electrodeposited copper foil as set forth in claim 2 or 3, wherein said rough surface is further formed with a copper plating layer.

5. An electrodeposited copper foil as set forth in
20 claim 2 or 3, wherein said rough surface is further formed with a copper plating layer and at least one layer of nickel plating, zinc plating, cobalt plating, plating of an alloy of the same and a chromate treatment layer on that, and according to need further formed with a
25 coupling agent treatment layer.

6. An electrodeposited copper foil as set forth in claim 1, wherein said rough surface having said knob-like projections and said surface roughness of 2 to 4 μm is a surface of an untreated copper foil for bonding with a resin substrate and is further formed with a copper plating layer and at least one layer of nickel plating, zinc plating, cobalt plating, plating of an alloy of the same and a chromate treatment layer on that, and according to need further formed with a coupling agent treatment layer.

7. A method of producing an electrodeposited copper foil comprising electrolysis using an electrolyte containing copper as a main component and a compound having mercapto groups, at least one type of another organic compound, and chloride ions to form a copper foil wherein part of its surface comprises a rough surface having knob-like projections and a surface roughness of 2 to 4 μm .

8. A method of producing an electrodeposited copper foil as set forth in claim 7, wherein an electroforming bath for a roughening treatment is an acidic electroforming bath containing at least one of molybdenum, cobalt, nickel, iron, tungsten and arsenic.

9. A method of producing an electrodeposited copper foil comprising producing an electrodeposited

copper foil having a matte side having a surface roughness of 2 to 4 μm using an electrolyte containing a compound having mercapto groups, at least one type of another organic compound, and chloride ions and

5 roughening treating said matte side of said electrodeposited copper foil by running a predetermined current through it for a predetermined time in an electroforming bath.